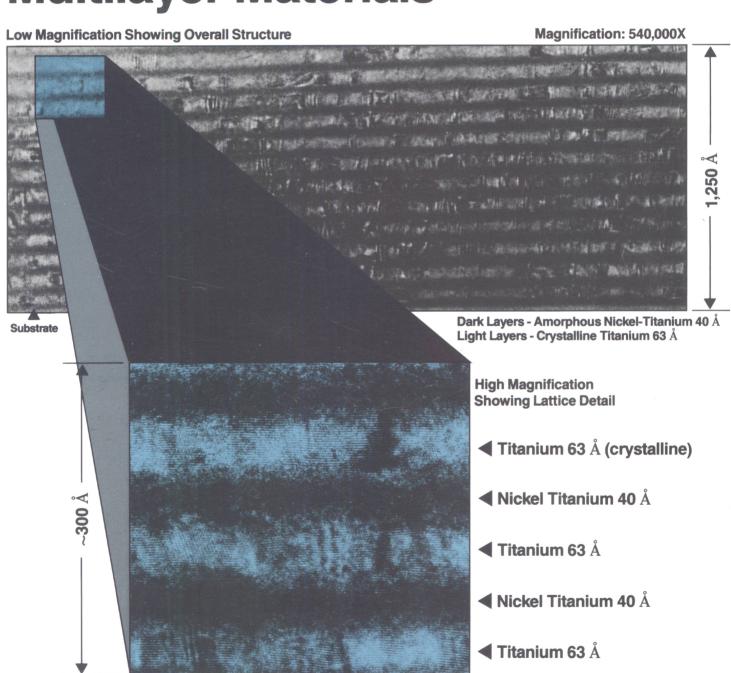
February 1990

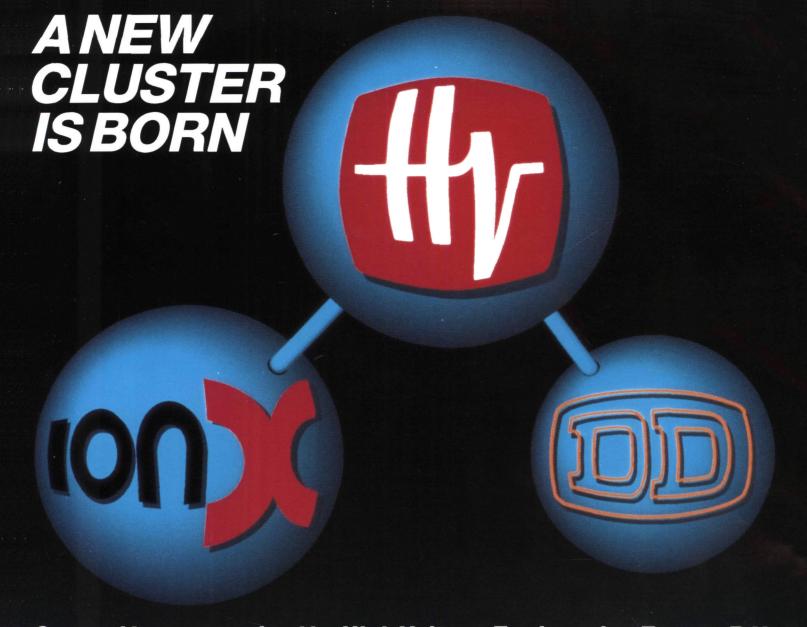
Volume XV, Number 2

Serving the International Materials Research Community

Multilayer Materials



Magnification: 2,700,000X



General Ionex acquired by High Voltage Engineering Europa B.V.

In December 1987 High Voltage Engineering Europa B.V. (HVEE) acquired Dowlish Developments Ltd (DD), an accelerator tube manufacturer located in the United Kingdom.

On April 10, 1989, HVEE purchased the General Ionex Analytical Product Group from Genus Inc. based in the United States.

Through this acquisition HVEE positions itself as the largest and most diverse manufacturer of particle accelerators for the scientific and industrial research communities.

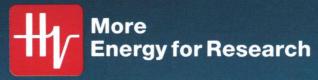
The acquired General Ionex (GI) product lines, which include the Tandetron accelerator systems and Model 4175 RBS Analyser, will be manufactured in HVEE's new, well-equipped facility in Amersfoort, The Netherlands.

World wide marketing of all products from HVEE, DD and GI will originate from HVEE Amersfoort with sales and service offices in the USA, Europe and Japan.

After addition of the newly acquired products HVEE's product lines include:

- Ion Accelerator Systems
 - Air insulated accelerators up to 500 kV
 - Single ended Van de Graaff accelerators up to 4 MV
 - Tandem Tandetron accelerators up to 3 MV/TV
- Research ion implanters
 - Beam energies 10 keV-9 MeV and higher
- Systems for ion beam analysis
 - Systems for RBS, PIXE, PIGE, NRA, ERD, MACS and MEIS
- Components
 - HV power supplies, electron and ion accelerator tubes, ion sources beamline components, beam monitoring equipment, UHV sample manipulators, etc.

For further information on this transaction and product literature please contact HVEE in Amersfoort/NL.



HIGH VOLTAGE ENGINEERING EUROPA B.V.

P.O. Box 99, 3800 AB Amersfoort, The Netherlands, Phone: (+31) 33 - 619741. Fax: (+31) 33 - 615291. Telex: 79100 HIVEC NL Sales Office for USA & CANADA: Peabody Scientific, P.O. Box 2009, Peabody, MA 01960, USA Phone: (508) 535-0444, Fax: (508) 535-5827



February 1990

A Publication of the Materials Research Society

Volume XV, Number 2 ISSN: 0883-7694 CODEN: MRSBEA

MULTILAYER MATERIALS

- 17 Multilayer Materials
 Troy W. Barbee Jr., Guest Editor
- 19 Metastable Phase Formation in Thin Films and Multilayers

Bruce M. Clemens and Robert Sinclair

29 Artificially Layered Superconductors

Ivan K. Schuller, J. Guimpel, and Y. Bruynseraede

37 Multilayer Optics for the Soft X-Ray and Extreme Ultraviolet

Troy W. Barbee Jr.

SPECIAL FEATURE

63 Upclose: Center for Advanced Materials Processing at Clarkson University

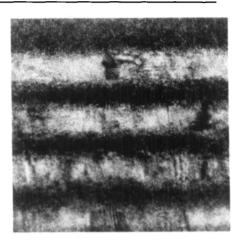
S.K. Ellis and E.P. McNamara Jr.

<u>MRS NEWS</u>

- 46 Preview: 1990 Spring Meeting
- 53 Chianelli Assumes MRS Presidency in 1990
- 56 Boston Meeting Attracts Worldwide Audience
- 61 Paul Siffert Receives Woody Award
- 61 Graduate Student Award Winners Honored at Fall Meeting
- 62 MRS Council Meets in Boston

DEPARTMENTS

- 4 Material Matters
- 7 Research/Researchers
- 12 Research Resources
- 15 From Washington
- 16 Editor's Choice
- 66 Historical Note
- **68** Section News
- **69** Chapter News
- 72 Book Reviews
- **73** Advertisers in this Issue
- 74 Calendar
- 78 Classified



ON THE COVER: Transmission electron lattice image of a titanium (Ti) - nickel titanium (NiTi) multilayer synthesized by magnetron sputtering. The multilayer contains 100 periods of 63 Å Ti and 40 Å NiTi. The Ti layers are crystalline with a (00.1) fiber texture while the NiTi layers are amorphous. The (00.1) Ti planes are lattice imaged in this micrograph. The grazing incidence thermal neutron reflectivity of this multilayer microstructure superlat-tice was measured to be >95% using facilities at the National Institute for Science and Technology. Model calculations predict thermal neutron reflectivities of ~99.6% as the neutron optical constants of Ti and Ni are very well suited to this application. The micrograph was taken by Mark A. Wall of Lawrence Livermore National Laboratory using a top-entry JEOL 200 CX transmission electron microscope at the National Center for Electron Microscopy, Lawrence Berkeley Laboratory.

ISIBI II I FI

Materials Research Society • 9800 McKnight Road • Pittsburgh, PA 15237

MRS BULLETIN

Editor G. A. Oare

(412) 367-3036

Assistant Editor F. M. Wieloch

(412) 367-3036 Copy Editor S. W. Morelli

Design/Production C. Love, W. Appman (412) 367-3003

Editorial Assistant J. Dininny (412) 367-3036

Advertising and Circulation

M. E. Kaufold (412) 367-3036 Associate Editor—Europe

I. W. Boyd

University College London Dept. of Electronic and **Electrical Engineering** Torrington Place London WCI E7 JE **United Kingdom** 01-387-7050 ext. 3956 or 7304

Contributor K. J. Anderson

Guest Editor T. W. Barbee Jr.

1990 MRS EXECUTIVE COMMITTEE

President

R. R. Chianelli Exxon Research and Engineering

First Vice President and **President-Elect**

J. B. Roberto Oak Ridge National Laboratory

Second Vice President

S. Carqill IBM T.J. Watson Research Center Secretary C.M. Jantzen

Westinghouse Savannah River Co.

Treasurer S. M. Kelso Therma-Wave, Inc.

Immediate Past President

R. P. H. Chang Northwestern University

Executive Director Materials Research Society John B. Ballance

EUROPEAN MRS

P. Siffert

Centre de Recherches Nucléaires Laboratoire PHASE 67037 Strasbourg, Cedex, France Telephone: (88) 28 65 43 Fax: (88) 28 09 90

Chairman—Editorial Boards

E. N. Kaufmann

Argonne National Laboratory Argonne, Illinois

International Advisory Board

M. Balkanski

University of Pierre and Marie Curie Pennsylvania State University

Paris, France

S. Hsu

Chung Shan Institute of Science and Technology

Taiwan, China

R. Krishnan

Defense Research and **Development Organization**

New Delhi, India

Tsinghua University Beijing, China

R. Roy

University Park, Pennsylvania

G. D. W. Smith University of Oxford Oxford, United Kingdom

T. Sugano University of Tokyo Tokyo, Japan

J. S. Williams

Royal Melbourne Institute of

Technology Melbourne, Australia

Technical Editorial Board

J. C. C. Fan Kopin Corporation Taunton, Massachusetts

Argonne National Laboratory Argonne, Illinois

G. L. Liedl **Purdue University** West Lafayette, Indiana

S. Namba Osaka University Osaka, Japan

R. L. Schwoebel

Sandia National Laboratories Albuquerque, New Mexico

R. C. Sundahl Intel Corporation Chandler, Arizona

K. C. Taylor General Motors Warren, Michigan

MRS BULLETIN

Publications Subcommittee

M. H. Bennett-Lillev Texas Instruments Dallas, Texas

R. R. Chianelli Exxon Research and Engineering AT&T Bell Laboratories

Annandale, New Jersey

R. J. Eagan Sandia National Laboratories Albuquerque, New Mexico

P. Sliva General Electric Largo, Florida

J. M. Phillips Murray Hill, New Jersey

C. W. White

Oak Ridge National Laboratory Oak Ridge, Tennessee

ABOUT THE MATERIALS RESEARCH SOCIETY

The Materials Research Society (MRS) is a nonprofit scientific association founded in 1973 to promote interdisciplinary goal-oriented basic research on materials of technological importance. Membership in the Society includes more than 9,500 scientists from industrial, government, and university research laboratories in the United States and more than 25 countries.

The Society's interdisciplinary approach to the exchange of technical information is qualitatively different from that provided by single-discipline professional societies because it promotes technical exchange across the various fields of science affecting materials development. MRS sponsors two major international annual meetings encompassing approximately 40 topical symposia, as well as numerous single-topic scientific meetings each year. It recognizes professional and technical excellence, conducts short courses, and fosters technical exchange in various local geographic regions through Section activities and University Chapters.

MRS is an Affiliated Society of the American Institute of Physics and participates in the international arena of materials research through associations
with professional organizations such as European MAS. MRS publishes symposium proceedings, the MRS BULLETIN, Journal of Materials Research, and other current scientific developments.

MRS BULLETIN (ISSN: 0883-7694) is published 12 times a year by the Materials Research Society, 9800 McKnight Road, Pittsburgh, PA 15237. Membership in MRS includes \$25.00 (\$15.00 for students) from membership dues to be applied to a subscription to the MRS BULLETIN. Application to mail at second class rates is pending at Pittsburgh, PA and at additional mailing offices. POSTMASTER: Send address changes to MRS BULLETIN in care of the Materials Research Society, 9800 McKnight Road, Pittsburgh, PA 15237; telephone (412) 367-3003; fax (412) 367-4373.

Back volumes of this publication are available in 16mm microfilm, 35mm microfilm, or 105mm microfiche through University Microfilms Inc., 300 North Zeeb Road, Ann Arbor, Michigan 48106.

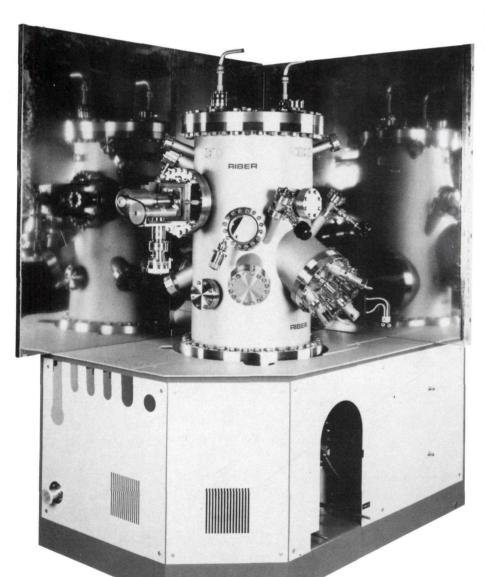
EVA 32

SUPERCONDUCTORS:

A PROVEN UHV DEPOSITION SYSTEM FOR SUPER-CONDUCTING THIN FILMS.

Superconducting thin films have been successfully grown and characterized in Riber systems for more than four years. Similar instrumental characteristics are required to grow the new high $T_{\rm c}$ materials:

- Precise substrate temperature control
- Precise composition control
- Impurity-free growth environment
- Flake-free growth chamber
- Compatible with any type of substrate
- Cuprate deposition process experience
- Refractory metal buffer layer capability
- Immediate analysis by XPS and Auger



Please visit Booth Nos. 212, 214 at the MRS Show in San Francisco, April 16-21, 1990.



For more information call (201) 494-8660

Riber Division of Instruments SA, Inc. 6 Olsen Avenue, Edison, NJ 08820 Telex 844516 FAX (201) 494-8796

RIBER, Division d'Instruments S.A. 133-137, boulevard National Rueil-Malmaison, France B.P. 231 — 92503 Rueil Cedex Tel. (1) 47.08.92.50 — Telex 203.367F

Printed in USA 1M 1987